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Docket No. AME-T114
Serial No. 10/694,453Remarks

Claims 1 and 27-100 are pending in this application and are before the Examiner for consideration.

Applicant requests that the second occurrence of equation 5 which was added to the specification by the Amendment filed January 17, 2007, be deleted. As noted by the Examiner, this equation was properly added by previous amendment.

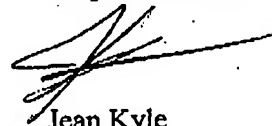
Claims 78-81, 99 and 100 have been rejected under 35 U.S.C. §112, second paragraph. Claims 78, 79 and 81 have been amended to address the informalities recited in the Action. Reconsideration and withdrawal of the rejection to these claims is therefore respectfully requested.

The Office Action indicates that claims 1, 27-77 and 82-98 are allowed. By this Amendment, applicant requests that certain of these claims be amended. The amendments note that the plasma source can be not only a metal vapor plasma source but also a sputter deposition plasma source. The amendments are supported by the base claim and provide consistency amongst the claims. No new matter is added by the proposed amendments and applicant respectfully requests entrance of these amendments into the record.

In view of the foregoing amendments, the applicant believes that the claim is now in condition for allowance and such action is respectfully requested.

Applicant invites the Examiner to call the undersigned if clarification is needed on any of this response, or if the Examiner believes a telephone interview would expedite the prosecution of the subject application to completion.

Respectfully submitted,



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